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# Effect of heat treatment on structure and magnetic properties of the Fe–N and Fe–Ti–N alloy films

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## Abstract

Fe–N and Fe–Ti–N alloy films have been prepared by reactive sputtering. The structure and magnetic properties of the Fe–Ti–N and Fe–N films have been studied as a function of the  $N_2$  flow rate  $R(N_2)$  and annealing temperature  $T_A$  by X-ray diffraction (XRD) and a vibrating sample magnetometer. The as-prepared and annealed Fe–N films consist of the  $\alpha$ -Fe and  $Fe_3N$  phases but the Fe–Ti–N films are composed of the  $\alpha$ -Fe and  $Ti_2N$  phases. The coercivity,  $H_c$ , of the Fe–N films changes drastically with  $R(N_2)$  and  $T_A$ , while that of the Fe–Ti–N films does not change with  $T_A$  up to 500 °C. These results indicate that the addition of Ti suppresses the formation of iron nitride phases and improves the thermal stability of Fe–N films. © 1997 Elsevier Science S.A.

**Keywords:** Structure; Magnetic properties; Sputter-deposition; Annealing; Fe–N film; Fe–Ti–N film

## 1. Introduction

Much attention has been paid to Fe–N films because of their excellent magnetic properties and the significant improvement of corrosion- and wear-resistance in comparison with pure iron [1–7]. Soft magnetic properties of Fe–N films were ascribed to reduction of grain size and decrease of magnetic anisotropy dispersion, caused by addition of a small amount of nitrogen [8]. However, Fe–N films show high magnetostriction and poor thermal stability, and their good soft magnetic properties disappear with increases in the heating temperature owing to grain growth of the refined iron. Recently, the addition of third elements to form ternary Fe–M–N systems ( $M = Ta, Zr, Hf, Nb, \dots$ ) [9–13] has succeeded in overcoming these weak points. The effects of a small amount of Ti doping to Fe–N [14] and Fe–Co–N [15] films on soft magnetic properties and magnetostriction have been investigated. However, the magnetic properties of Fe–N and Fe–Ti–N alloy films with relatively large amount of Ti and N have not been reported.

In this study, the Fe–N and Fe–Ti–N alloy films were prepared on a water-cooled substrates by a facing-target-type DC sputtering (FTS) system at different nitrogen flow ratios  $R(N_2)$ , and then as-prepared films were annealed at

various temperatures. The change of the structure and magnetic properties after annealing have been investigated.

## 2. Experimental

Fe–N and Fe–Ti–N alloy films were deposited on glass substrates by the FTS system in a mixed Ar+ $N_2$  plasma, using a composite target consisting of pure Fe (99.9%) and Ti (99.9%) plates. The Fe and Ti concentration ratio was adjusted by changing the ratio of the surface area of Fe and Ti plates: the ratio of the surface area is Fe:Ti=7:3 in this study. In order to obtain Fe–Ti–N films with various nitrogen contents the relative  $N_2$  flow rate,  $R(N_2) = [N_2\text{-flow rate}] / [Ar\text{-flow rate} + N_2\text{-flow rate}]$  (in %), was adjusted by fine control of mass flow meters of  $N_2$  and Ar gas. The substrate during the sputtering deposition was kept at about 50 °C by indirect water cooling. The sputtering conditions are listed in Table 1. The chemical composition (listed in Table 2) of deposited films was determined by inductively coupled plasma (ICP) optical emission spectrometry and helium carrier fusion-thermal conductivity methods. The annealing of as-prepared films is carried out in a vacuum ( $5 \times 10^{-5}$  Torr) between 200 and 600 °C for 1 h, where the heating and cooling rates are  $5^\circ C \text{ min}^{-1}$ .

Structures of the films were analyzed by X-ray diffrac-

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Table 1  
Sputtering condition

Background pressure	$<4 \times 10^{-4}$ Pa
Total pressure	$9.3 \times 10^{-1}$ Pa
Nitrogen flow ratio	0-30%
Input power	0.95 kW
magnetic field	
At the target center	$8 \text{ kAm}^{-1}$
At the target edge	$12 \text{ kAm}^{-1}$
Substrate temperature	Water cooling
Substrate	Glass and polyimide
Deposition rate	$\sim 1.0 \text{ nm s}^{-1}$

tion with CuK $\alpha$  radiation using a graphite monochromator. Magnetic properties of the films were measured by a vibrating sample magnetometer (VSM) in a magnetic field up to 10 kOe applied parallel to the plane of the films in the temperature range of 0-900 °C.

### 3. Results

#### 3.1. Structure

Fig. 1 shows X-ray diffraction patterns of the Fe-Ti-N and Fe-N films sputter-deposited under the same deposition conditions (see Table 1) using the Fe-Ti composite target or Fe target. For Fe-Ti-N films (Fig. 1(a)), the (110) peaks shift to a lower  $2\theta$  side (the lattice expands). Broadening of diffraction peaks indicates a tendency of amorphous phase formation and/or refinement of crystal grains as  $R(N_2)$  increases. In the Fe-N films (Fig. 1(b)), no  $\gamma'$ -Fe $_4$ N phase is formed at  $R(N_2)=10\%$  but formed evidently at  $R(N_2)=20$  and 30%. Moreover, the different preferred-orientation of the  $\gamma'$ -Fe $_4$ N phase in two films is observed.

The X-ray diffraction patterns of the Fe-N films annealed at  $T_A=400$  °C for 1 h are shown in Fig. 2. The amount and the grain size of  $\gamma'$ -Fe $_4$ N phase increases, comparing with the as-prepared films (Fig. 1(b)).

Fig. 3 shows the X-ray diffraction patterns of the Fe-Ti-N films deposited at  $R(N_2)=30\%$  after annealing at

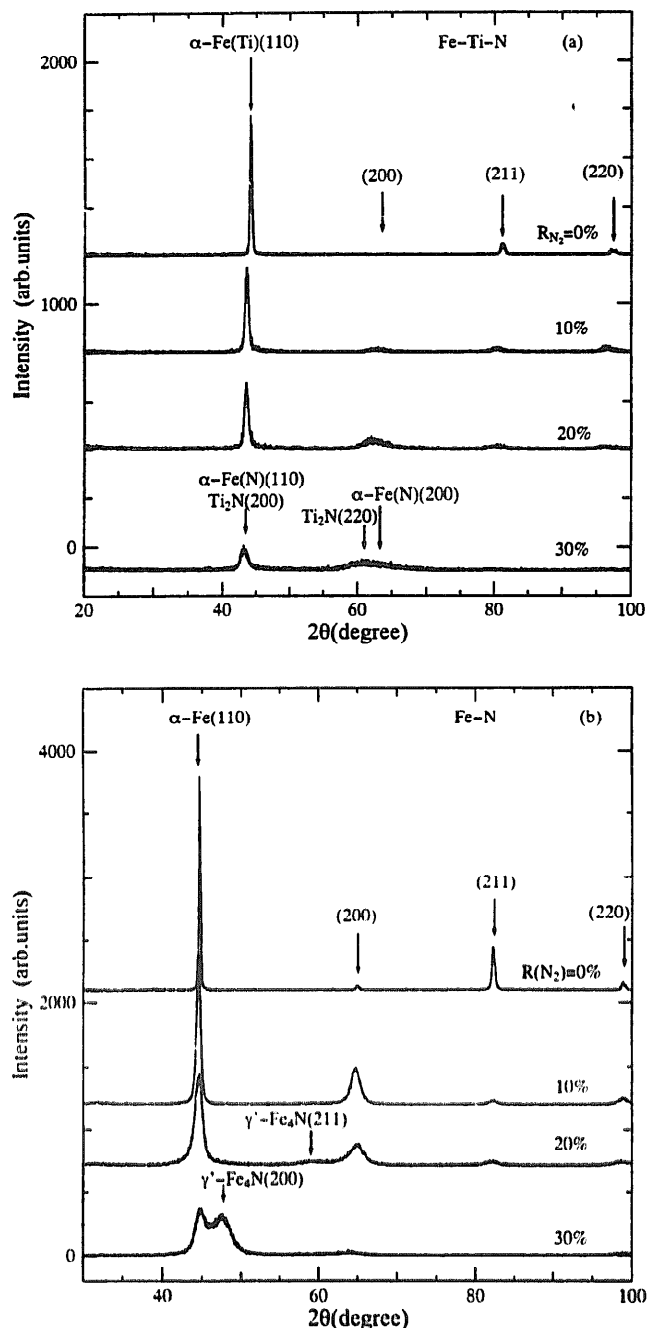


Fig. 1. X-ray diffraction patterns of the Fe-Ti-N (a) and Fe-N (b) films deposited on water-cooled substrates at  $R(N_2)=0, 10, 20$  and 30%.

Table 2

Composition analysis results of the Fe-N and Fe-Ti-N films

Target	$R(N_2)$ (%)	Fe (at.%)	Ti (at.%)	N (at.%)
Fe	0	100		
	10	98.1		1.9
	20	94.5		5.5
	30	87.1		12.9
Fe:Ti=7:3	0	89.7	10.3	
	10	88.6	8.3	3.1
	20	87.1	7.0	5.9
	30	83.9	4.9	11.2

$T_A=400, 500$  and  $600$  °C for 1 h. The annealed films are composed of the  $\alpha$ -Fe and  $Ti_2N$  phases. The increase in the intensity and sharpness of the diffraction peaks clearly indicate that the large  $\alpha$ -Fe grain is formed after the annealing at  $T_A>500$  °C.

The lattice constants,  $a$ , calculated from the interplanar distance,  $d_{110}$ , of  $\alpha$ -Fe(110) are plotted versus  $R(N_2)$  in Fig. 4 for as-prepared and annealed Fe-Ti-N and Fe-N films. The values of  $a$  of the Fe-Ti-N films are always larger than those of pure Fe and Fe-N films. They increase

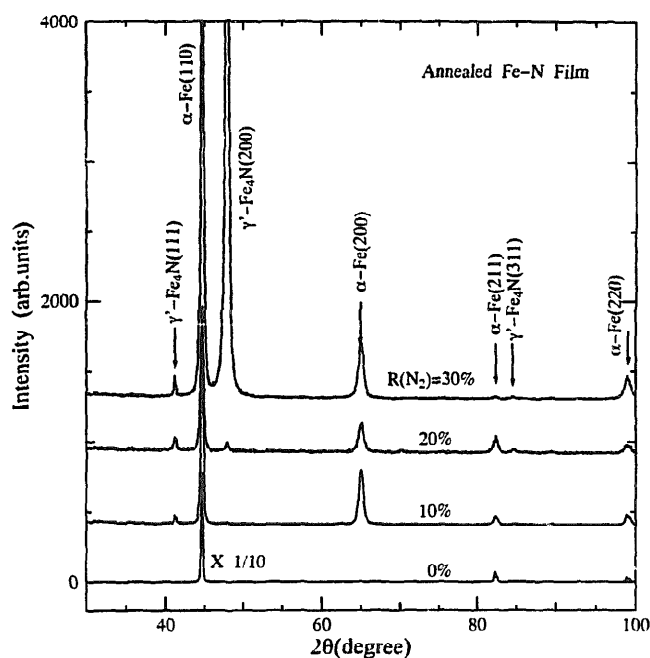


Fig. 2. X-ray diffraction patterns of the Fe–N films annealed at 400 °C for 1 h.

with increasing  $R(N_2)$ . Moreover, The  $a$  values of the annealed Fe–Ti–N films decrease, being accompanied by the grain growth. For the as-prepared Fe–N films, the lattice constant first increases slightly because of the expansion of  $bcc$ , and then decreases because of the phase transformation from the  $\alpha$ -Fe phase to the  $\alpha'$  phase with

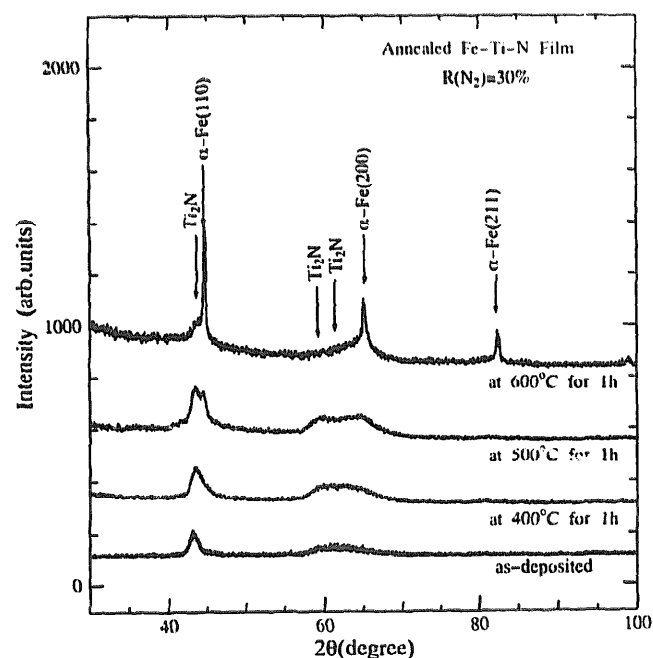


Fig. 3. The change of X-ray diffraction patterns of the Fe–Ti–N films deposited at  $R(N_2)=30\%$  with the annealing temperature as a parameter.

increasing  $R(N_2)$  [17]. After annealing at 400 °C, there are the same  $a$  values for all Fe–N films due to growth of the  $\alpha$ -Fe grain size, phase transformation from the  $\alpha'$  phase to the  $bcc$  phase and formation of the  $\gamma'$ -Fe<sub>3</sub>N phase.

### 3.2. Temperature dependence of magnetic properties

Fig. 5(a) and (b) show the saturation magnetization,  $M_s$ , and coercivity,  $H_c$ , for the as-prepared and 400 °C annealed Fe–Ti–N and Fe–N films as a function of  $R(N_2)$ . From Fig. 5(a), the  $M_s$  values of the annealed Fe–Ti–N films deposited at  $R(N_2)=10$  and 20% are larger than those of the as-prepared films, while there is no change in  $M_s$  for  $R(N_2)=0$  and 30%. No evident change in  $H_c$  can be observed for all Fe–Ti–N films before and after annealing. The  $H_c$  first decreases and then increases with increasing  $R(N_2)$ . For the as-prepared Fe–N films (Fig. 5(b)), the  $M_s$  first increases slightly and then decreases with increasing  $R(N_2)$ . The increase in  $M_s$  is ascribable to the expansion of the  $\alpha$ -Fe lattice owing to the incorporation of N atoms and the decrease to formation of the  $\gamma'$ -Fe<sub>3</sub>N phase [6,7]. The  $M_s$  values of the annealed Fe–N films deposited at  $R(N_2)=10$  and 20% are smaller than those of the as-prepared films but there is no change in  $M_s$  for  $R(N_2)=0$  and 30%. This means that transformation from the  $\alpha'$  phase to the  $bcc$  phase and formation of the  $\gamma'$ -Fe<sub>3</sub>N phase after annealing give a same contribution to  $M_s$  for the Fe–N film deposited at  $R(N_2)=30\%$ . The  $H_c$  values of the as-prepared Fe–N films increase as increasing  $R(N_2)$ :  $H_c = 90$  Oe for  $R(N_2)=30\%$ . This can be considered as the occurrence of lattice distortion in the films due to incorporation of nitrogen atoms. It is further confirmed by the decrease in  $H_c$  of the annealed Fe–N films. The annealed Fe–N films have a about same  $H_c$  value.

Fig. 6(a) and (b) show the temperature dependence of magnetization for the Fe–Ti–N and Fe–N films in a magnetic field of 5 kOe. Fig. 6(a) indicates that there are two magnetic transformation in the Fe–Ti–N film for  $R(N_2)=0\%$ , and the Curie temperature,  $T_c = 703$  and 540 °C, respectively, while  $T_c = 730$  °C for the Fe–Ti–N films deposited at  $R(N_2)=10, 20$  and 30%. In contrast to the Fe–Ti–N films, the temperature dependence of magnetization for Fe–N films is more complicated (as shown in Fig. 6(b)). The highest  $T_c$  value is about 746 °C and there is a magnetic transformation at about 440 °C because of existence of the  $\gamma'$ -Fe<sub>3</sub>N phase in the films. Moreover, for the Fe–N film deposited at  $R(N_2)=30\%$ , the magnetization disappears suddenly in the temperature range from 580 to 680 °C due to phase transformation from  $bcc$   $\alpha$ -Fe to  $fcc$   $\gamma$ -Fe and the decomposition of the  $\gamma'$ -Fe<sub>3</sub>N phase at about 570 °C. Although the Fe–N equilibrium phase diagram predicts that decomposition temperature of the  $\gamma'$ -Fe<sub>3</sub>N phase is about 680 °C, the lower temperature decomposition is probably due to instability of the non-equilibrium Fe–N films.

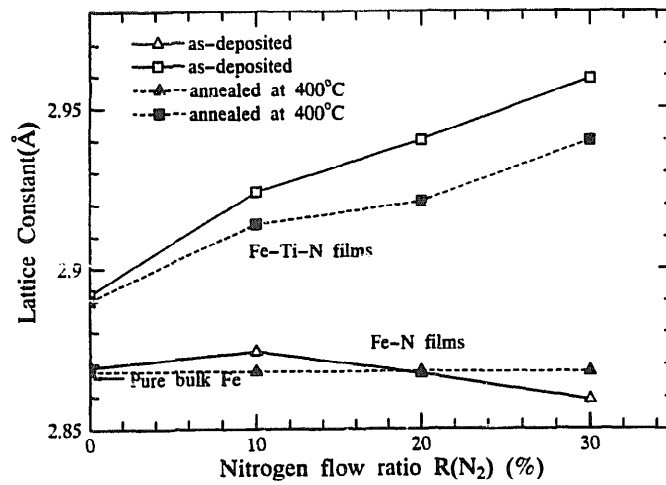


Fig. 4. The change of lattice constant before and after annealing at 400 °C for the Fe-Ti-N and Fe-N films deposited at  $R(N_2)=0, 10, 20$  and  $30\%$ .

4. Discussion

Fig. 1(a) indicates that Ti atoms apparently dissolve substitutionally and nitrogen atoms interstitially in bcc Fe lattices below  $R(N_2)=20\%$ . At  $R(N_2)=30\%$ , the very broad X-ray diffraction peaks obviously suggest formation

of a second phase. The previous X-ray photoelectron spectroscopy (XPS) results have showed that the broad (110) peak for the Fe-Ti-N film deposited at  $R(N_2)=30\%$  is allotted to the  $\alpha$ -Fe phase with a very small grain size and the  $TiN_x$  phase [16]. It has been proved further that the  $TiN_x$  phase is the  $Ti_2N$  phase through the change in

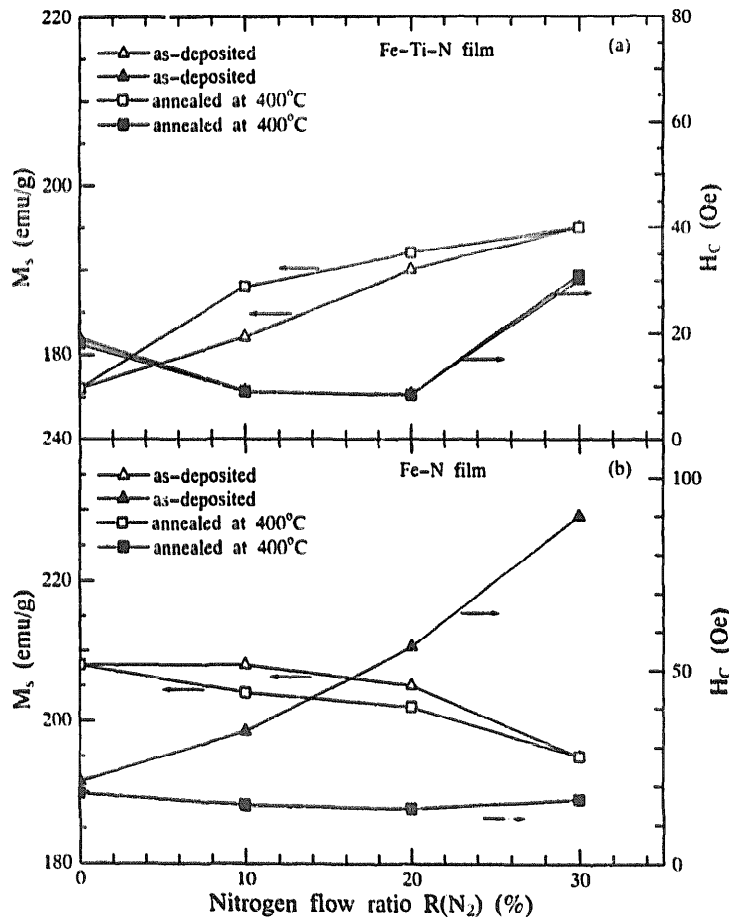


Fig. 5. Variation of saturation magnetization  $M_s$  and coercivity  $H_c$  before and after annealing at 400 °C for the Fe-Ti-N (a) and Fe-N (b) films deposited at  $R(N_2)=0, 10, 20$  and  $30\%$ .

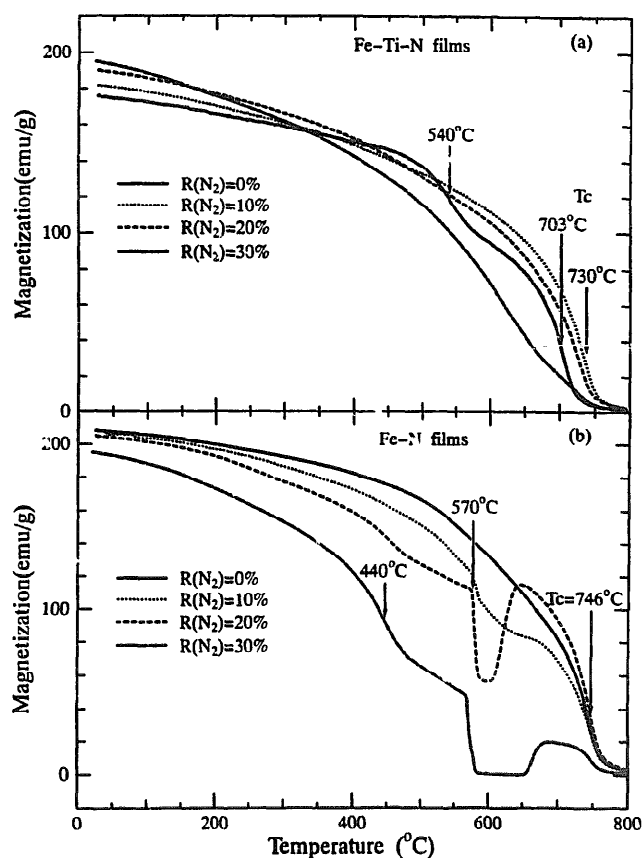


Fig. 6. Heating curves of magnetization for the Fe-Ti-N (a) and Fe-N (b) films deposited at  $R(N_2) = 0, 10, 20$  and  $30\%$  in a magnetic field of  $5 \text{ kOe}$ .

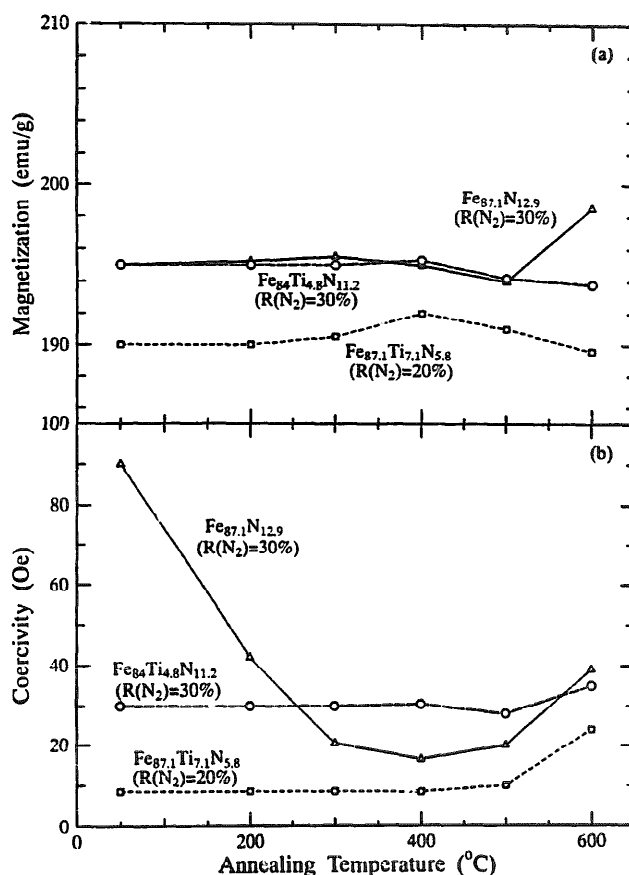


Fig. 7. Dependence of saturation magnetization  $M_s$  (a) and Coercivity  $H_c$  (b) on annealing temperature for the Fe-Ti-N films deposited at  $R(N_2) = 20$  and  $30\%$  and Fe-N film deposited at  $R(N_2) = 20\%$ .

structure of the film as increasing annealing temperature (Fig. 3). No evidence has been found for Fe-N compounds in the deposited Fe-Ti-N films up to  $R(N_2) = 30\%$ . A sufficient amount of Ti seems to inhibit the formation of iron nitride phases on annealing. The peak broadening with increases  $R(N_2)$  could be due to the small grain size and peak splitting associated with the tetragonal distortion of  $\alpha$ -Fe by interstitial nitrogen atoms.

The formation of the  $\gamma'$ - $\text{Fe}_4\text{N}$  phase can have been observed in annealed Fe-N film deposited at the lower  $R(N_2) = 10\%$  (Fig. 2). In the Fe-Ti-N films, on the other hand, there is no observable change in the structure after annealing at  $400^\circ\text{C}$  for 1 h (not shown here). This demonstrates the good thermal stability in the magnetic properties in the Fe-Ti-N films.

As shown in Fig. 4, the change of the lattice constant in the Fe-N films corresponds to the phase transformation from the  $\alpha$ -Fe phase to the *bct* martensite ( $\alpha'$ ). Therefore, it is easily understood that the incorporation of nitrogen atoms results in lattice distortion of the  $\alpha$ -Fe phase and causes a monotonic increase in  $H_c$  with increasing  $R(N_2)$  for the as-prepared Fe-N films (Fig. 5(b)). For the as-prepared Fe-Ti-N films, however, the  $H_c$  first decreases and then increases with increasing  $R(N_2)$  (Fig. 5(a)). This is ascribed to distortion of  $\alpha$ -Fe lattice due to doping of Ti

atoms and compressive stress caused by the incorporation of sufficient nitrogen atoms [16].

Fig. 7(a) and (b) show the dependence of the saturation magnetization  $M_s$  and coercivity  $H_c$  on  $T_A$  for the Fe-Ti-N and Fe-N films. In the Fe-Ti-N films,  $H_c$  shows almost no change for  $T_A < 500^\circ\text{C}$  and slightly increases for  $T_A = 600^\circ\text{C}$  because the grain size grows obviously (as shown Fig. 3). In the Fe-N film, on the other hand, the  $H_c$  first decreases drastically and then increases with increasing  $T_A$ . The decrease in  $H_c$  is ascribed to reduction of compressive stress due to formation of the  $\gamma'$ - $\text{Fe}_4\text{N}$  phase. The increase in  $H_c$  results from the grain growth. The variation in  $M_s$  for both Fe-Ti-N and Fe-N films is not obvious below  $500^\circ\text{C}$  and the increase of  $M_s$  of the Fe-N films after annealing at  $600^\circ\text{C}$  is ascribed to decomposition of the  $\gamma'$ - $\text{Fe}_4\text{N}$  phase.

## 5. Conclusions

The effects of heat treatment on the structure and magnetic properties of the Fe-Ti-N and Fe-N films prepared under the same deposition condition have been investigated. The large amount of Ti doping into Fe-N

film suppresses the formation of iron nitride phases even after annealing at 600 °C and expands the bcc lattice. For the Fe–Ti–N films, there is a tendency of forming amorphous phase as increasing  $R(N_2)$  and the  $Ti_2N$  phase is formed at  $R(N_2)=30\%$ . Compared with the Fe–Ti–N films, the formation of the  $\gamma'$ - $Fe_3N$  phase in the Fe–N films before and after annealing and the decomposition of the  $\gamma'$ - $Fe_3N$  phase cause a poor thermal stability in the magnetic properties in the Fe–N films. The decomposition temperature of the  $\gamma'$ - $Fe_3N$  phase in non-equilibrium Fe–N films is about 570 °C. The second magnetic transformation temperatures are 540 °C in the Fe–Ti film and 440 °C in the Fe–N films.

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